

U.S. Serial No. 09/501,114

## PATENTS

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: )  
 Tzeng ) Group Art Unit: 1762  
 Serial No: 09/501,114 ) Examiner: Markham, W.  
 Filed: February 10, 2000 ) Docket No.: A029 1080  
 For: Method of Plasma Enhanced )  
 Chemical Vapor Deposition of )  
 Diamond )

Assistant Commissioner For Patents  
 Box Amendment  
 Washington, D.C. 20231

Dear Sir:

In response to the office action dated July 25, 2001, please amend the subject application as follows.

IN THE SPECIFICATION

On page 7, starting at line 17, please delete the paragraph and insert in place thereof the following:

The substrate generally is sheet or wafer of silicon, copper, aluminum and molybdenum.

Some of the substrates are polished using 1  $\mu$ m diamond paste prior to the deposition process.

Typically, the substrate is mounted on a water cooled substrate holder. The substrate can be either in touch with the plasma or at a distance from the plasma. In experiments using the